

ATLAS Phase-II High Luminosity UK Planar Pixel Sensors

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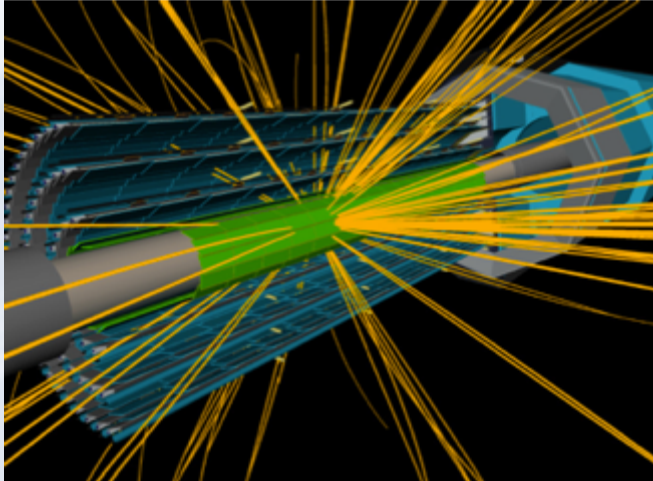
On behalf of the UK ATLAS Pixel Upgrade group

University of Liverpool



MICRON SEMICONDUCTOR Ltd





Luminosity upgrade to LHC driven by

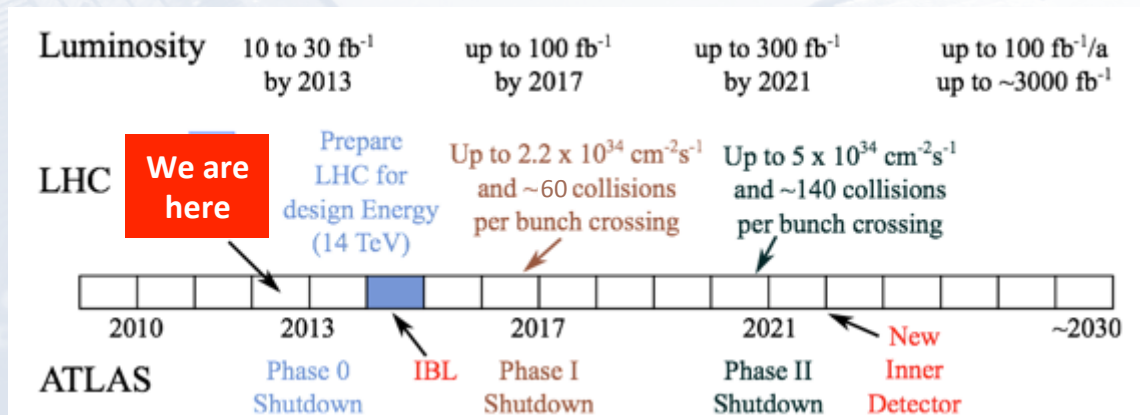
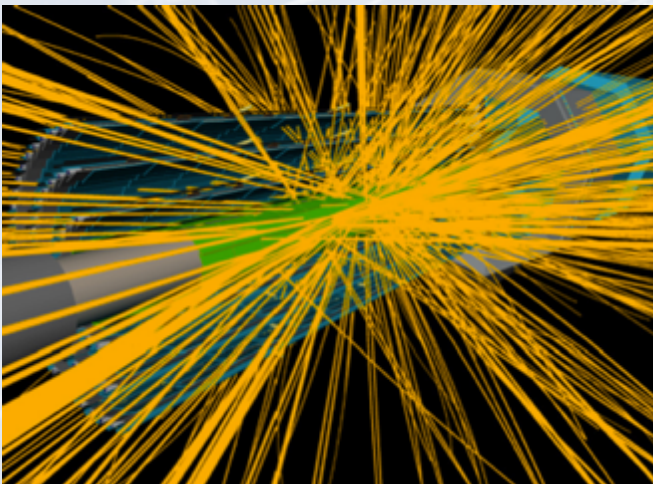
Desire to reduce statistical uncertainties

Desire to increase search for new physics at higher energy via lower probability events

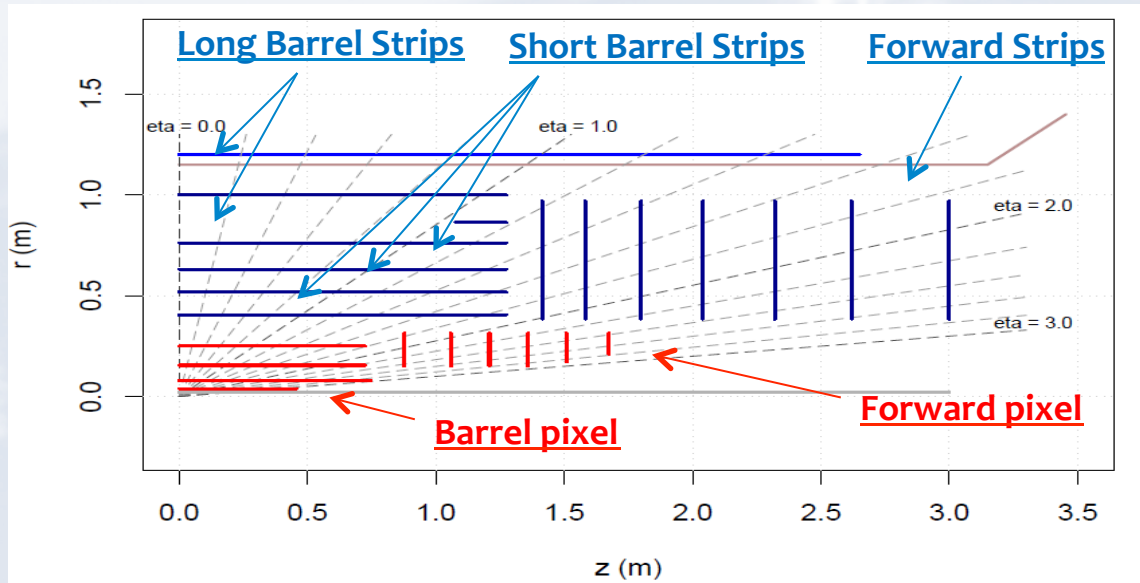
Luminosity increase by an order of magnitude

Corresponding increase in occupancy (depends on luminosity leveling)

Radiation damage to a maximum of $2 \cdot 10^{16}$ 1MeV n_{eq}/cm^2



Phase-II ATLAS ITk baseline layout



- 4 pixel barrel layers
 - Radius from 39 mm to 250 mm
 - Z: ± 449 mm to ± 694 mm (outer 2 layers)
- 6 Pixel disks
 - $R_{\text{inner}} = 150$ mm
 - $R_{\text{outer}} = 315$ mm
 - Z: 820 mm to 1890 mm

2 outer Pixel Barrel layers / Disks

Sensor

planar n-in-p
150 μm

Pixel size 50 μm x 250 μm

ROC (ReadOut Chip) thickness 150 μm

ToT (Time over threshold) = 4 bits

2x2 (Quad) and 2x3 (Hex) chip modules

Data rates of 640 Mbit/s per module

2 Inner Pixel Barrel layers

– Sensors

PPS and 3D – Diamond, n-in-n/n-in-p silicon
150 μm silicon/diamond or thinner

– Pixel size 25 μm x 150 μm

– ROC (ReadOut Chip) thickness 150 μm

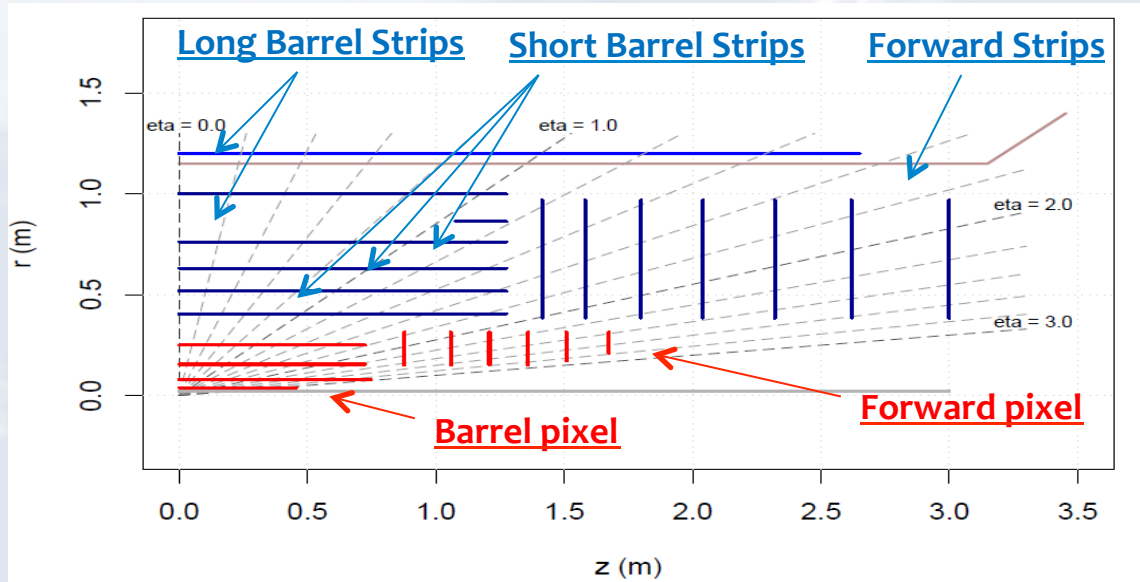
– ToT (Time over Threshold) = 0-8 bits

– 2x1 and 2x2 chip modules

– 2x2 sensor = 33.9 mm x 40.6 mm

– Data rate as high as 2 Gbit/s per module

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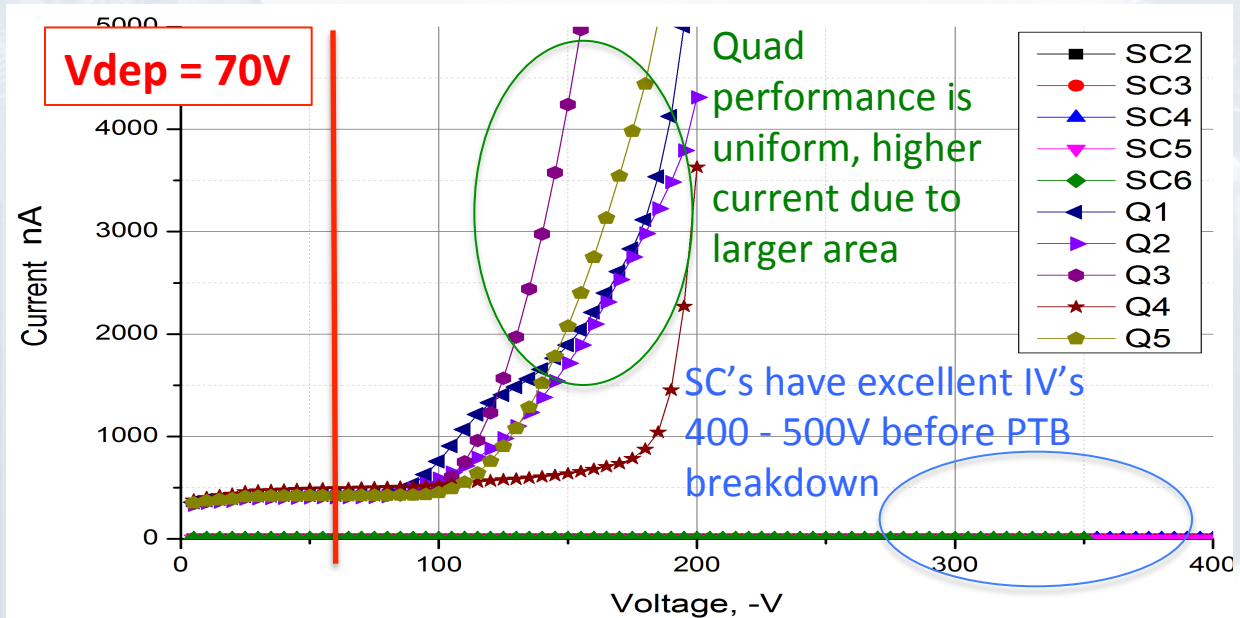
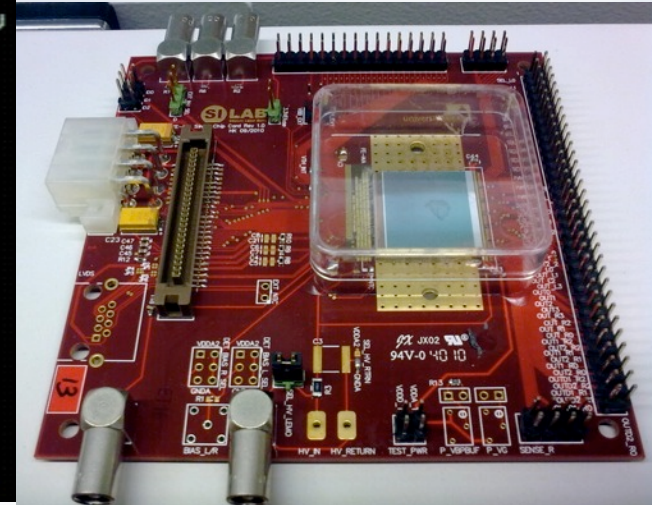
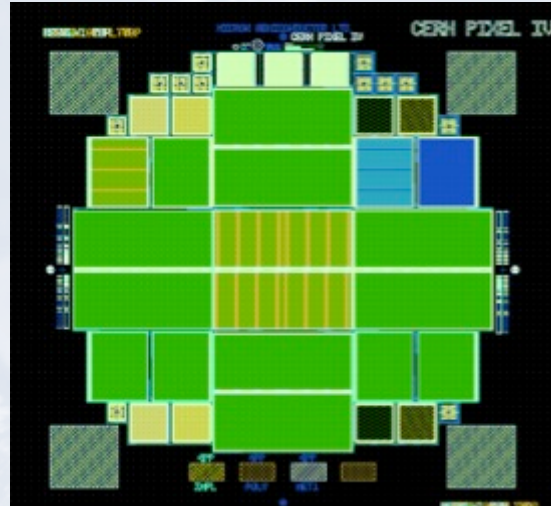
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– Data rate as high as 2 Gbit/s per module

- Sensors produced by Micron Semiconductors LTD based in Worthing, UK
- ATLAS IBL FE-I4 ROC used
- General silicon resistivity used $\sim 10\text{k}\Omega$, $300\mu\text{m}$ thick
- Single and Quad FE-I4 compatible sensors
 $V_{\text{dep}} = 70\text{V}$

- All sensors show reduced current after flip chipping by a factor of 5-10 times less than on die IV measurements, Punch Through Bias is bypassed after bump bonding



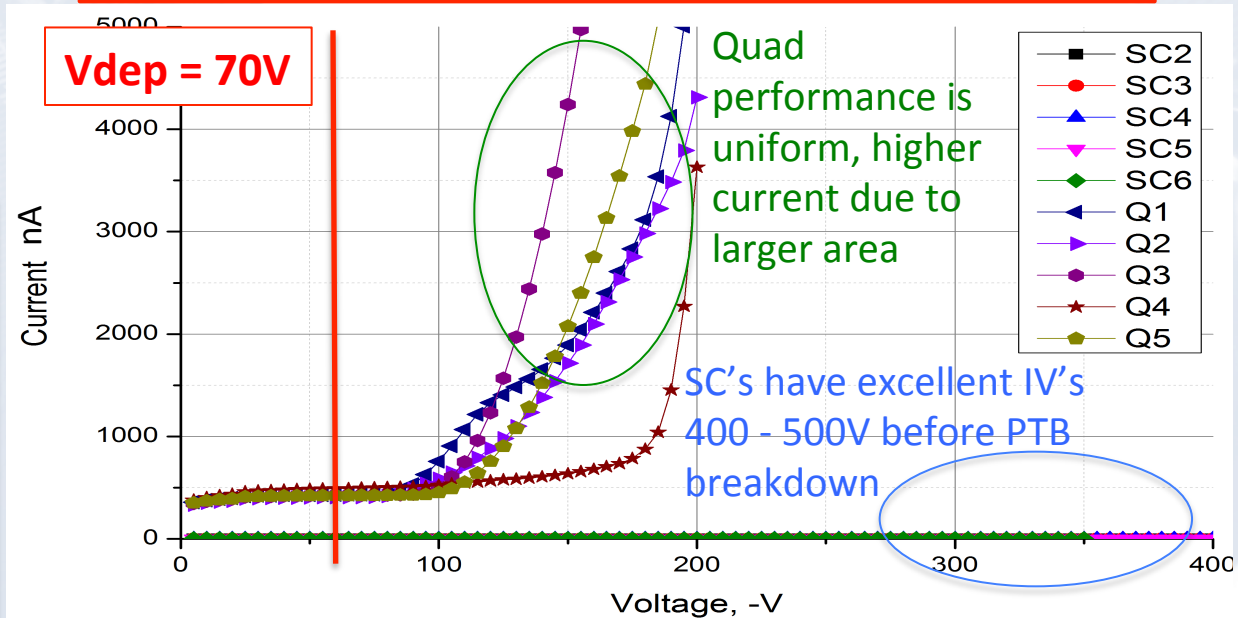
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Quad sensor on rigid test board has leakage current of $\sim 80\text{nA}$ with all four ROC's powered, with sensor at -100V

On die wafer IV measurements at -100V are around 500nA

The cause is high bias dot density for pre bump bond testing – required by ATLAS



Non-standard designs for Phase-II

Liverpool CERN Pixel V wafer - Test vehicle for different layouts and structures. All compatible with FE-I4

Disks

Square pixels may be an advantage for tracking

Large radius use strips

Lower position resolution requirements
Lower power and cost

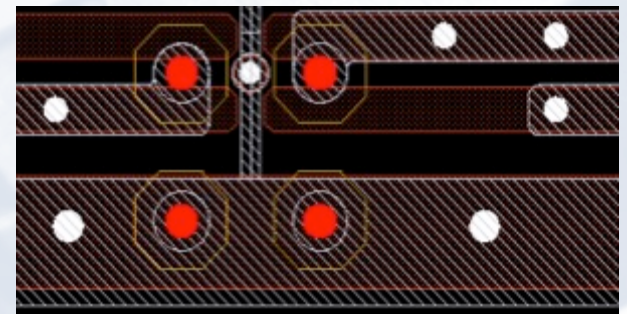
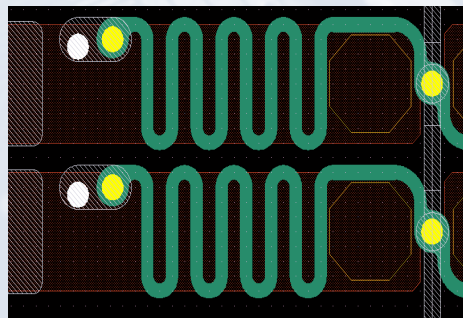
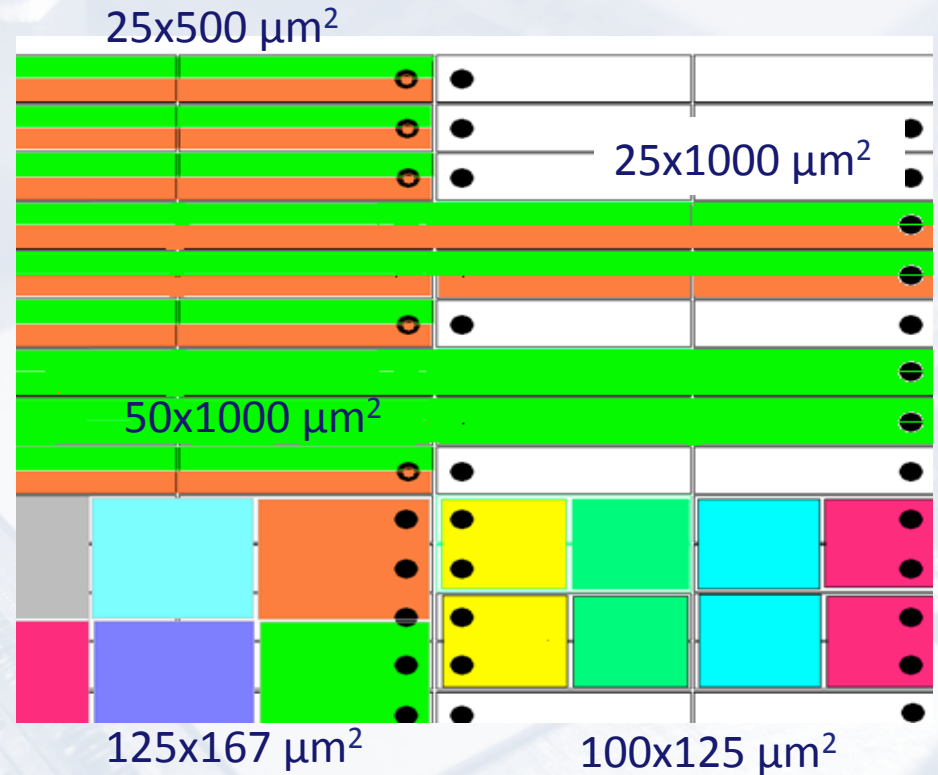
Long large area implants

Turn off some pixels to save cost
Lower density flip-chip to reduce cost

Bias dot optimization to increase detection efficiency after high radiation dose

Poly-silicon bias structures

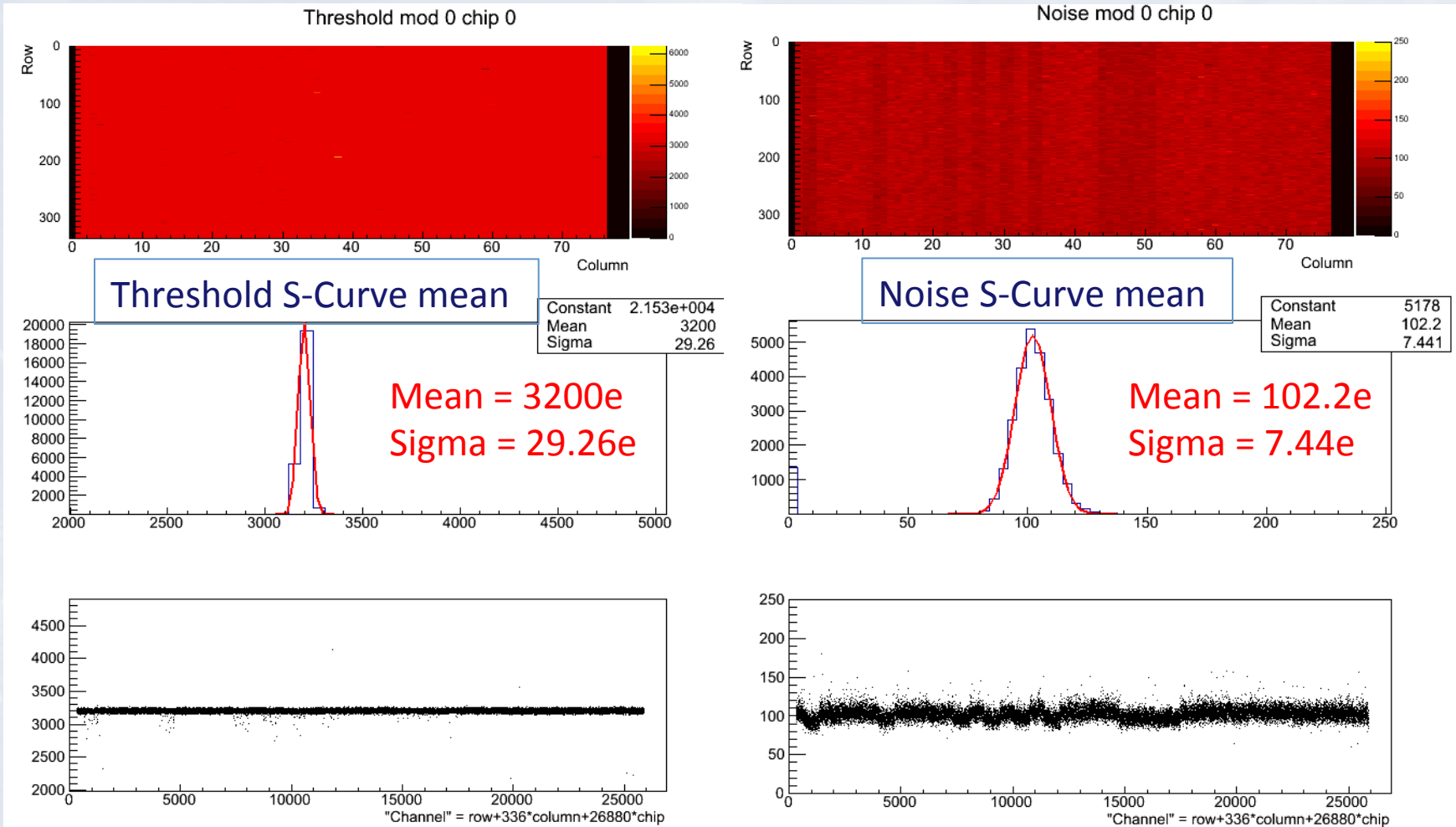
Remove bias dot completely
AC couple detectors possible



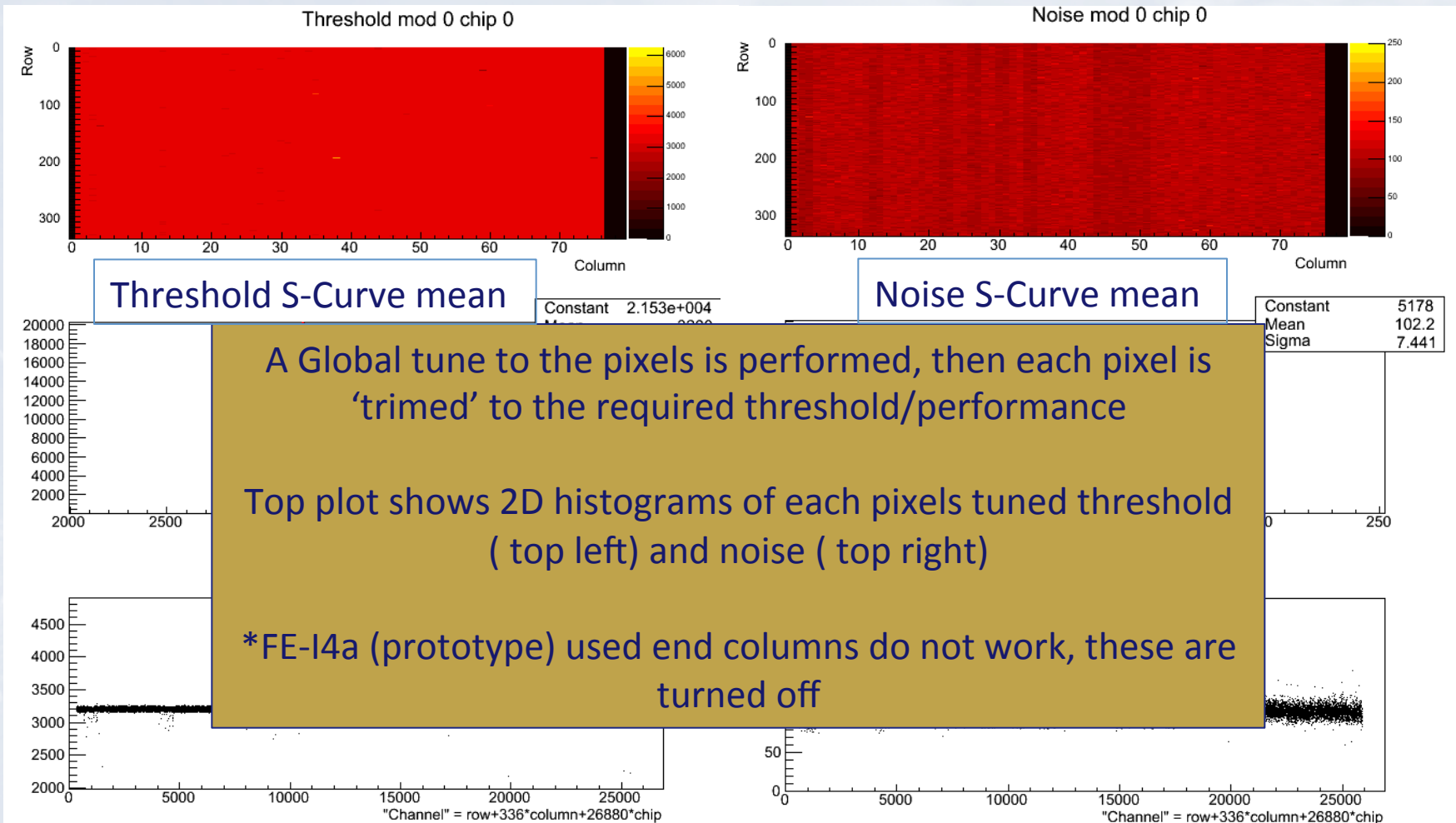
- Quads are roughly 4x4cm (singles 2x2cm)
- Only group to have a dedicated QUAD sensor design.
- UK have 4 fully bumped QUAD assemblies
- 2 have been irradiated to $5E15n_{eq}/cm^2$ in CERN's PS before shutdown, awaiting testing. Modifications to the Liverpool rigid test card needed
- 1 QUAD has been glued to a Bonn flex and mounted onto a rigid card for multiplexing testing.
- 1 QUAD mounted on a rigid test card similar to the SC rigid card IBL sensors used, Sensor can be unmounted without breaking wire bonds from ROC
- A Further 10 QUADs to be produced in 2013 for use in building a pixel disk segment



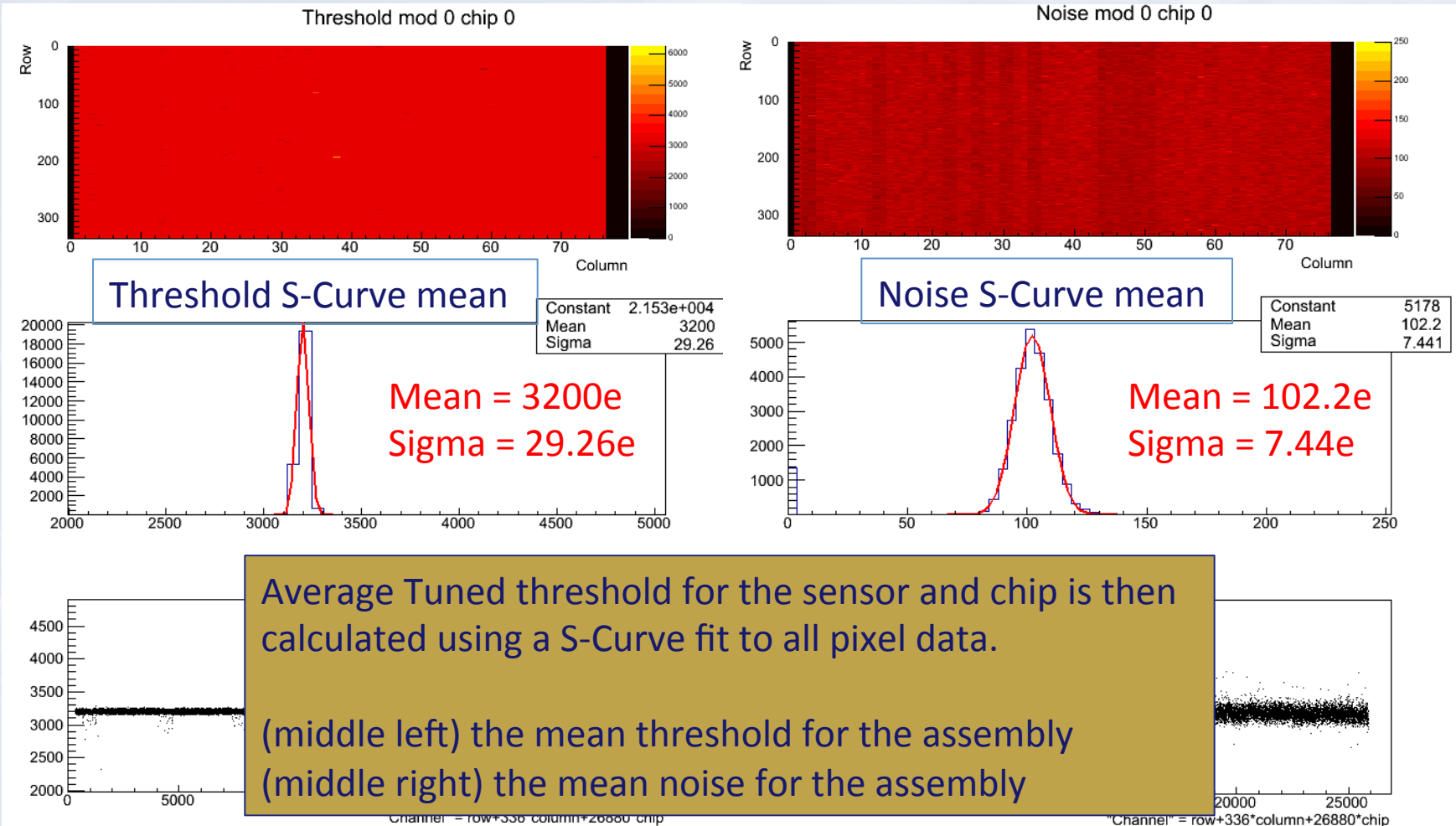
Each device tuned for in-time threshold, 3200e then tuned down to lower thresholds. ToT (Time Over Threshold) is calibrated according to device thickness but will not be shown



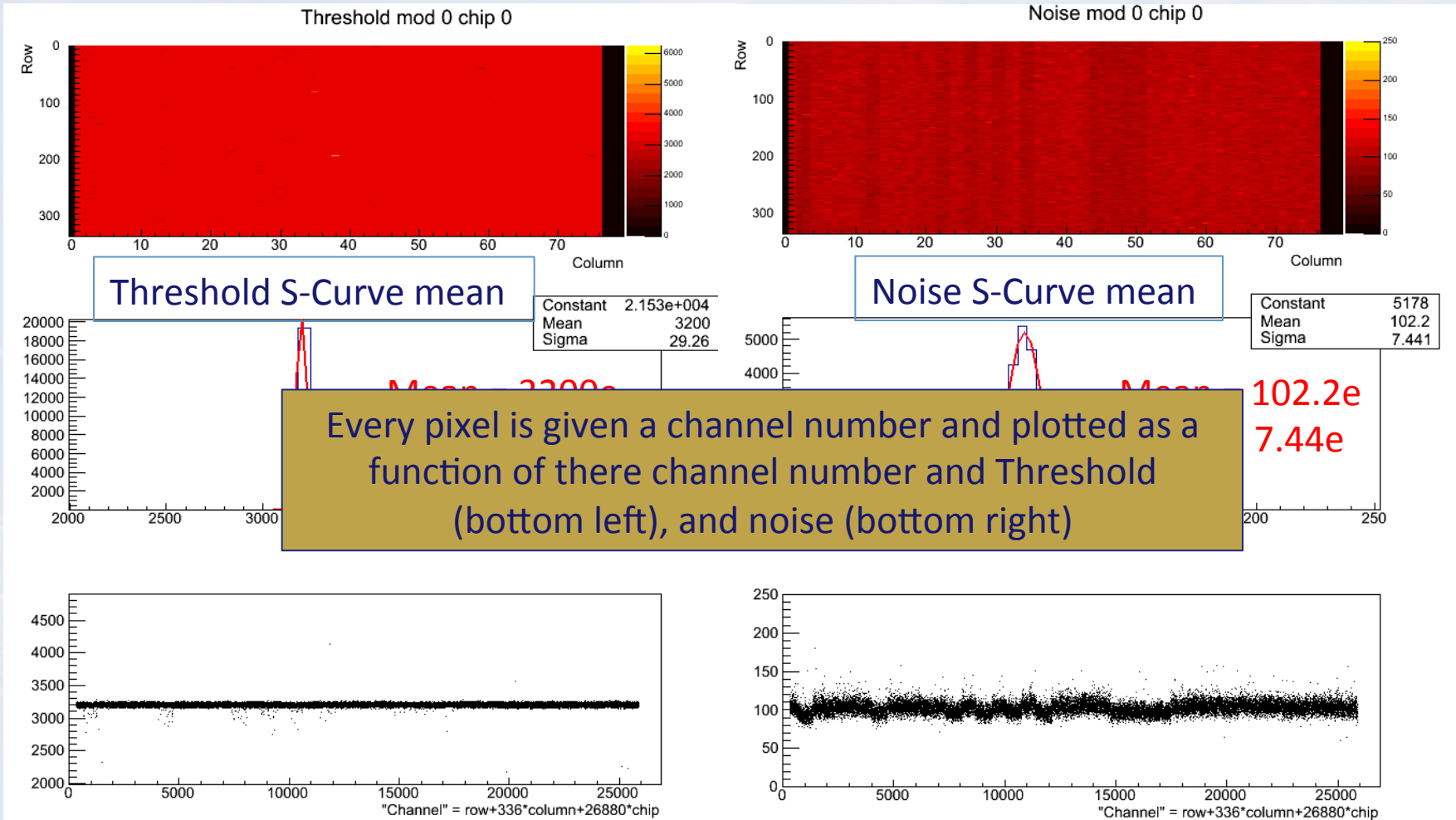
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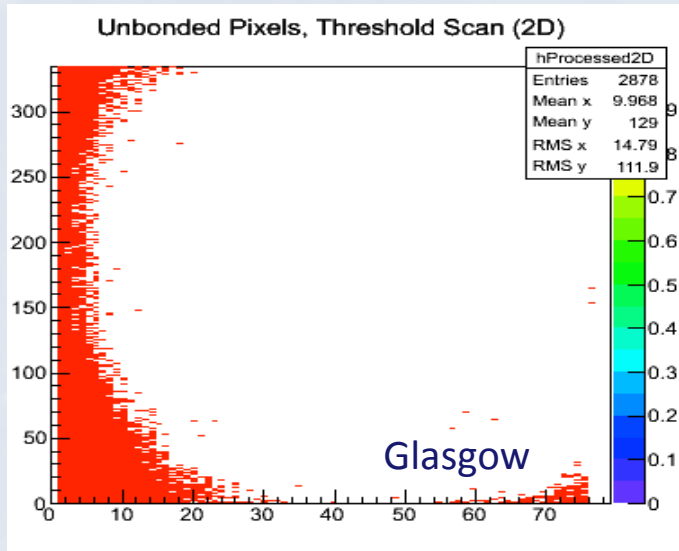
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Pre bump bonding thinned ROC's show some disconnected pixels, due to roc bowing with temperature



Large areas of non-boned pixels at the corners & edges (only for very thin readout chips)

Disconnected pixels are rare for full thickness ROC's and for post bumped thinned ROC and sensors for single and quad sensors

Bump Process Flow

1. Deposit UBM and bumps on ROIC
2. Thin ROIC to 200 μm / Diced
3. On vacuum jigs perform flip-chip for tack bond
4. Re-flow in reducing atmosphere in oven (260C) unsupported assembly
 - Self-align bumps
 - Obtain good electrical properties

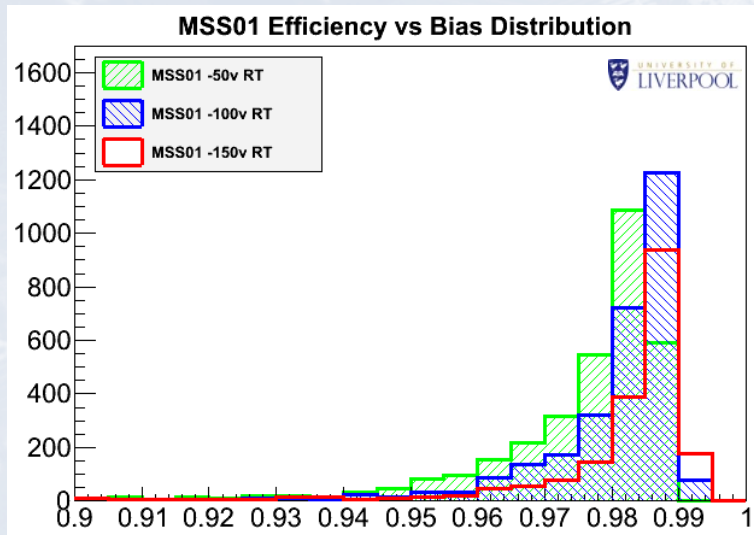
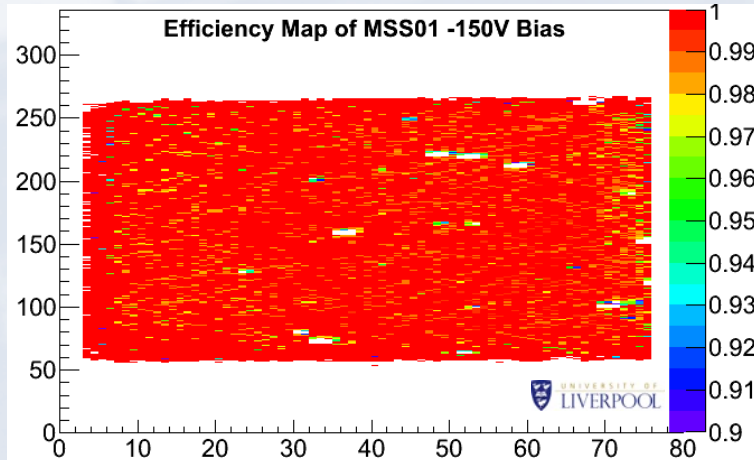
ROIC bows due to non-symmetric layers

- Thick dielectric layers on top side
- Just silicon on back side

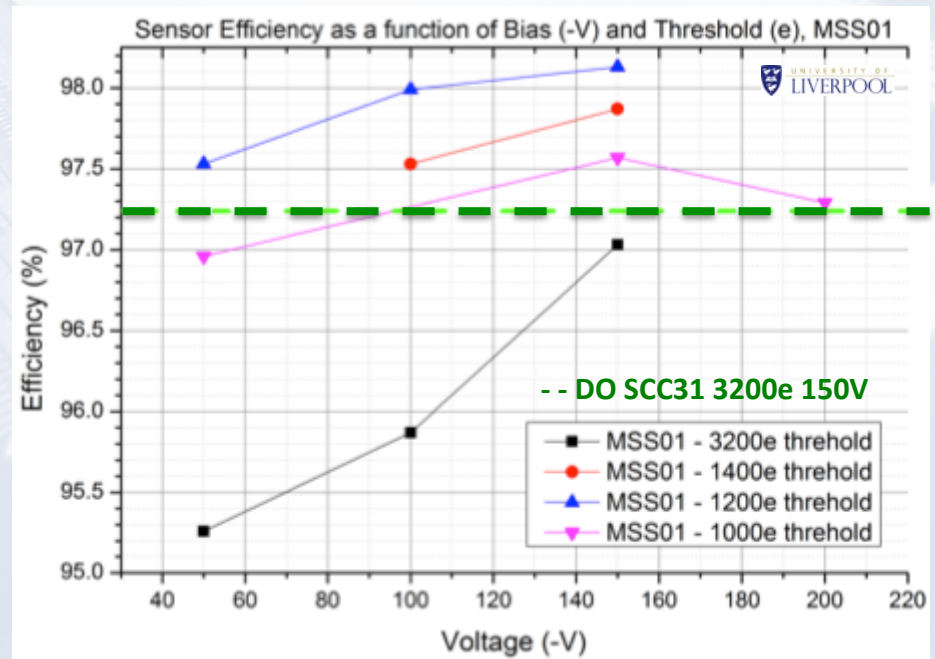
Solution under investigation

- Support wafer technology
- Deposition of balancing dielectric on ROIC

DESY – 4GeV Positrons



- Devices are tested for high tracking efficiency vs Bias voltage and tuned Threshold
- high hit efficiency seen even for under depleted devices
- High hit efficiency important at low threshold operation to benefit from charge sharing after irradiation without losing hits that would normally be under threshold



- Production of new Liverpool Cern Pixel 5 wafer, (square pixels, strixels, increased $R\phi$ resolution sensors), Liverpool/Micron
- Irradiated Quad tests (2 irradiated quads at $5E15$ $1\text{MeV } n_{\text{eq}}/\text{cm}^2$), Liverpool
- Testbeam data reconstruction/analysis, Liverpool
- Quad/Hex Module multiplexing, Manchester
- Thin ROC support wafer/ backside dielectric for production flip chipping, Glasgow
- FE-I4a/b wafer probing (FE-I4 ROC pass/fail), Glasgow/Edinburgh
- Pixel disk segment prototype mechanics/structure, Liverpool, Manchester, Glasgow
- Disk tapes, Edinburgh
- Wafer cleaning and passivation of FE-I4 wafers and material identification of pads, RAL
- Flip chipping, RAL
- Flex serial powering, RAL

Micron 6inch FE-I4 single and quad sensors available for production with high yield
300, 200, 150, 100 μ m thick, and n-in-n and n-in-p geometry types

Assemblies with flip-chip VTT

Excellent assembly IV characteristics

Problems at the edge due to bow with low bump yield

Quad module

Preliminary tests are very promising, first group to have a dedicated design

Testbeam analysis

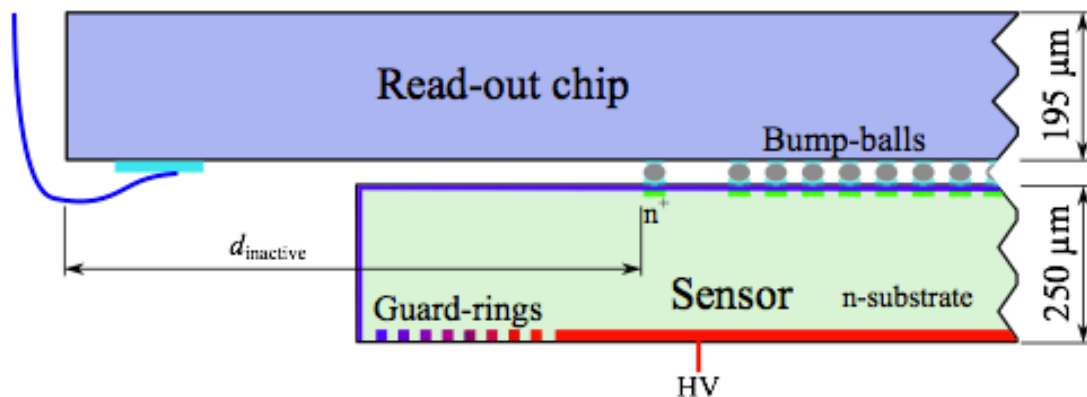
Work under way into publishing test beam data for standard and non
standard single and quad modules

ATLAS PPS 2012 and 2013 results papers

As well as general R&D papers for the quad and other designs



BACKUP



Sensor design

- DOFZ Si n-substrate, 250μm thick
- Read-out chip planar n+-in-n pixels, 400x50μm²
- 16 guard rings on p side to shape HV step
- 1.1 mm inactive edge incl. safety margin

Read-out and interconnection

- FE-I3: 2880 channels
- DC coupled and bump bonding
- Shaper + Amplifier + Discriminator
- $ToT \propto Charge$

